

L Number	Hits	Search Text	DB	Time stamp
1	62	(((((shallow adj trench adj isolation) or STI)) and (photo\$lresist or resist)) and ((hydrogen or H?sub.2) same (anneal or annealling or thermal\$3 or treat\$3))) and (etch or etching)) and (polish or polishing or cmp or planarizie or (etch\$3 adj back))) and (epitaxial or epitaxy)	USPAT	2003/09/26 09:25
-	5896	((shallow adj trench adj isolation) or STI)	USPAT	2003/09/25 14:02
-	3069	((shallow adj trench adj isolation) or STI)) and (photo\$lresist or resist)	USPAT	2003/09/25 14:03
-	799	((shallow adj trench adj isolation) or STI)) and (photo\$lresist or resist)) and (hydrogen or H?sub.2)	USPAT	2003/09/25 14:06
-	655	((shallow adj trench adj isolation) or STI)) and (photo\$lresist or resist)) and (hydrogen or H?sub.2)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4")	USPAT	2003/09/25 14:05
-	304	((shallow adj trench adj isolation) or STI)) and (photo\$lresist or resist)) and ((hydrogen or H?sub.2) same (anneal or annealling or thermal\$3 or treat\$3)))	USPAT	2003/09/25 14:06
-	295	((shallow adj trench adj isolation) or STI)) and (photo\$lresist or resist)) and ((hydrogen or H?sub.2) same (anneal or annealling or thermal\$3 or treat\$3))) and (etch or etching)	USPAT	2003/09/25 14:07
-	221	((shallow adj trench adj isolation) or STI)) and (photo\$lresist or resist)) and ((hydrogen or H?sub.2) same (anneal or annealling or thermal\$3 or treat\$3))) and (etch or etching)) and (polish or polishing or cmp or planarizie or (etch\$3 adj back))	USPAT	2003/09/25 16:26
-	144	((shallow adj trench adj isolation) or STI)) and (photo\$lresist or resist)) and ((hydrogen or H?sub.2) same (anneal or annealling or thermal\$3 or treat\$3))) and (etch or etching)) and (polish or polishing or cmp or planarizie or (etch\$3 adj back))) and ((trench or isolation or sti).ab. or (trench or isolation or sti).clm.)	USPAT	2003/09/25 14:10
-	19	("4582565" "4666556" "4671970" "5087586" "5244827" "5246537" "5248625" "5385861" "5387538" "5455194" "5472903" "5854120" "5895253" "5915191" "5926717" "5989977" "6001705" "6022789" "6358785").PN.	USPAT	2003/09/25 14:13
-	26	("3990927" "4474975" "5156881" "5182221" "5410176" "5470798" "5719085" "5741740" "5776557" "5786039" "5801083" "5863827" "5883006" "5888880" "5895253" "5904540" "5930645" "5943585" "5950094" "5960299" "5972773" "5998280" "6030881" "6051447" "6156674" "6300219").PN.	USPAT	2003/09/25 14:18
-	62	(((((shallow adj trench adj isolation) or STI)) and (photo\$lresist or resist)) and ((hydrogen or H?sub.2) same (anneal or annealling or thermal\$3 or treat\$3))) and (etch or etching)) and (polish or polishing or cmp or planarizie or (etch\$3 adj back))) and (epitaxial or epitaxy)	USPAT	2003/09/26 09:24